IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

e the Application of

Yasushi YAMAZAKI et al.

2811 Group Art Unit:

Application No.: 09/970,766

Shouxiang Hu Examiner:

Filed: October 5, 2001

Docket No.:

110791

For:

METHOD OF MANUFACTURING SEMICONDUCTOR SUBSTRATE,

SEMICONDUCTOR SUBSTRATE, ELECTRO-OPTICAL APPARATUS AND

ELECTRONIC EQUIPMENT

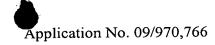
RESPONSE TO RESTRICTION REQUIREMENT

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

In reply to the Restriction Requirement mailed April 23, 2002, Applicants provisionally elect Group II, claims 1-9, drawn to a method of making a semiconductor device, classified in class 438, subclass 149, with traverse.

It is also respectfully submitted that the subject matter of all claims 1-16 is sufficiently related that a thorough search for the subject matter of any one group of claims would encompass a search for the subject matter of the remaining claims. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it is stated that "if the search and examination of the entire application can be made without serious burden, the Examiner must examine it on the merits even though it includes claims to distinct or independent inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicants and duplicative examination by the Patent Office.



Thus, withdrawal of the Restriction Requirement is respectfully requested.

Respectfully submitted,

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JAO:EDM/gam

Date: May 22, 2002

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